



NIL Industrialday 2019 (March 28 - 29, 2019) - PROGRAM

March 28th, 2019 - NIL Industrialday (Day 1)

11:00 - 11:30	REGISTRATION / NETWORKING AND EXHIBITION
11:30 - 12:20	LUNCH / NETWORKING AND EXHIBITION
12:20 - 12:30	OPENING, WELCOME AND AGENDA Michael Hornung, AMO GmbH & Gabi Grützner, micro resist technology GmbH
12:30 - 14:20	SESSION I: LIFE SCIENCES
12:30 - 13:00	KEYNOTE PRESENTATION: EPFL - Institute of Microengineering, Jürgen Brugger "Micro and nano engineering of fragile materials for solid applications"
13:00 - 13:20	Micronit Microtechnologies B.V., Aliko Tsopela "Replication techniques in the micro-nano scale for healthcare"
13:20 - 13:40	Profactor GmbH, Michael Haslinger "Magneto-plasmonic nanoparticles for biomolecular sensing fabricated by UV-NIL"
13:40 - 14:00	Universität Hamburg, Irene Hernandez-Cuesta "Lab-on-chip devices made of functional, UV imprintable polymers"
14:00 - 14:20	University of Glasgow, Nikolaj Gadegaard "Unlocking biomedical discovery through volume production of nanopatterned materials"
14:20 - 15:20	COFFEE / NETWORKING AND EXHIBITION
15:20 - 17:00	SESSION II: OPTICS AND PHOTONICS I
15:20 - 15:40	Yole Développement, Amandine Pizzagalli "NIL equipment trends and opportunities for photonic applications"
15:40 - 16:00	ams AG, Tobias Senn "NIL in mass production - from design to production"
16:00 - 16:20	WaveOptics Ltd., Dion Price "Unlocking augmented reality: The role of waveguide displays"
16:20 - 16:40	Dispelix Oy, Ismo Vartiainen "AR displays for smart glasses: Principles, prospects, and challenges"
16:40 - 17:00	Korea University, Heon Lee "DOE anticounterfeit devices fabricated using NIL"
17:00 - 18:00	DRINKS / NETWORKING AND EXHIBITION
18:30 20:00	SIGHTSEEING - (Cathedral's Treasury / Historic Old Town) CONFERENCE DINNER

March 29th, 2019 - NIL Industrialday (Day 2)

08:00-08:40	REGISTRATION / EXHIBITION
08:40 - 10:00	SESSION III: OPTICS AND PHOTONICS II
08:40 - 09:00	<i>Eurecat - Technology Centre of Catalonia, Claudia Delgado</i> "Printed waveguides in structural electronics for automotive lighting applications"
09:00 - 09:20	<i>SCIL Nanoimprint Solutions, Marc Verschuuren</i> "Feature placement and overlay accuracy in SCIL"
09:20 - 09:40	<i>SUSS MicroOptics SA, Reinhard Völkel</i> "Excellence in microlens imprint lithography and wafer-stacking for optical sensor and lighting applications"
09:40 - 10:00	<i>micro resist technology GmbH, Manuel Thesen, Jan Klein</i> "Reviewing recent case studies"
10:00 - 10:20	<i>EV Group GmbH, Christine Thanner</i> "NILPhotonics competence center - From idea to success with nanoimprinting"
10:20-11:20	COFFEE / EXHIBITION
11:20 - 12:40	SESSION IV: 3D PATTERNING AND MASTERING
11:20 - 11:40	<i>SwissLitho AG, Felix Holzner</i> "Grayscale mastering down to single nanometer resolution"
11:40 - 12:00	<i>NIL Technology ApS, Niklas Hansson</i> "Master fabrication with 2.5D and 3D structures for optical applications"
12:00 - 12:20	<i>CEA-LETI, Hubert Teysedre</i> "3D shallow profiles for silicon optical elements"
12:20 - 12:40	<i>AMO GmbH, Ulrich Plachetka</i> "3D shaping of nanopatterns by RIE etching"
12:40-13:30	LUNCH / EXHIBITION
13:30 - 14:30	SESSION V: GLOBAL NIL PERSPECTIVE
13:30 - 13:50	<i>A*STAR - Institute of Materials Research and Engineering, Vignesh Suresh</i> "Sustaining a vibrant nanoimprint ecosystem in Singapore"
13:50 - 14:10	<i>GermanLitho GmbH, Ran Ji</i> "Nanoimprint technology and market trends in China"
14:10 - 14:30	<i>temicon GmbH/Coatema Coating Machinery GmbH, Oliver Humbach, Thomas Kolbusch</i> "Upscaling for large area seamless UV-NIL for the Chinese market"
14:30	CLOSING